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April 16, 2004

To: Commissioner for Patents  
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Alexandria, VA 22313-1450

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28 Davis Avenue  
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Subject: | Serial No. 10/786,798 02/25/04 |

Kuo-Chi Tu et al.

SPACER PROCESS TO PREVENT THE  
REVERSE TUNNELING IN SPLIT GATE  
FLASH

#### INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation  
In An Application.

The following Patents and/or Publications are submitted to  
comply with the duty of disclosure under CFR 1.97-1.99 and  
37 CFR 1.56.

#### CERTIFICATE OF MAILING

I hereby certify that this correspondence is being  
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P.O. Box 1450, Alexandria, VA 22313-1450, on April 26, 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

 4/26/04

U.S. Patent 6,400,603 to Blyth et al., "ELectronically-Eraseable Programmable Read-Only Memory Having Reduced-Page-Size Program and Erase," discusses an array of FLASH electrically erasable programmable read-only memory cells having reduced-page-size erasing and programming.

U.S. Patent 6,617,638 to Chiang et al., "Tapered Floating Gate with Nitride Spacers to Prevent Reverse Tunneling During Programming in a Split Gate Flash," discloses a method of forming a split-gate flash memory cell with a tapered floating gate.

U.S. Patent 6,465,841 to Hsieh et al., "Split Gate Flash Memory Device Having Nitride Spacer to Prevent Inter-poly Oxide Damage," teaches a method to fabricate a split-gate flash memory cell with nitride spacers.

U.S. Patent 6,380,030 to Chen et al., "Implant Method for Forming Si<sub>3</sub>N<sub>4</sub> Spacer," discloses an implant method for forming a silicon nitride spacer.

U.S. Patent 6,031,264 to Chien et al., "Nitride Spacer Technology for Flash EPROM," discloses a nitride spacer for flash EPROM.

Sincerely,  
  
Stephen B. Ackerman, Reg. #37761

